

**REMARKS**

Claims 1-45 are pending in the present application. By this Preliminary Amendment, claims 38-45 have been added. Claims 1, 7, 12, 20, 28 and 36 are independent claims.

**Elected Claims**

In response to the Examiner's Restriction Requirement, Applicants elected on February 25, 2003 Group II having claims 36-37 for initial examination. Group II is directed to a method of controlling the thickness of a gate insulating layer, classified in class 438, subclass 1, as set forth in the Examiner's Office Action. However, ~~Applicants respectfully submit that at least claims 7-11 should be examined with~~ elected Group II claims since they are directed to substantially the same or similar subject matter as elected Group II. For instance, claims 9 and 11 specifically recite the use of an etching point detection window in the etching process. It is believed that the examination of at least claims 7-11 along with elected Group II claims would not place undue burden on the Examiner. Accordingly, reconsideration and examination of elected Group II claims and at least claims 7-11 is respectfully requested.

**New Claims**

New claims 38-45 further define the invention as recited in independent claim 36.

Entry of the above amendments is earnestly solicited. An early and favorable first action on the merits is earnestly solicited.

Should there be any matters which need to be resolved in the present application, the Examiner is respectfully requested to contact Esther H. Chong (Registration No. 40,953) at the telephone number of the undersigned below.

Attached hereto is a marked-up version of the changes made to the application by this Amendment.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. § 1.16 or under 37 C.F.R. § 1.17; particularly, extension of time fees.

Respectfully submitted,

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Attachments: Version with Markings to Show Changes Made

**VERSION WITH MARKINGS TO SHOW CHANGES MADE**

In the Specification:

The specification has been amended as follows:

On page 6, lines 3-6 have been amended as follows:

--The upper plate 6 includes [consists] of an upper glass substrate 30, color filters (not shown), a black matrix 28, and a common transparent electrode 26. As shown, the color filters and the black matrix 28 are formed on the upper glass substrate 30, and the common transparent electrode 26 is formed thereon.--

On page 16, lines 13-18 have been amended as follows:

--The area of the EPD window 104 is made much wider than the actual pattern area of the lower plate 70 so that reaction gas generated during etching is increased to make the detection of gas easier. The EPD window 104 is not limited to the area as shown in Fig. 12, but can be formed on a non-display part 110 of the lower plate 70 or between the pads 50 and 90 at a pad part 112, as shown in Fig. 13.--

On page 14, lines 5-9 have been amended as follows:

--Improvement can be made when defining the holes 56 or 94. In the above embodiment, the organic protective film 78 and the gate insulating film 74 are

etched to expose the lower glass substrate 72. However, during the actual etching process, a portion of the lower glass substrate 72 may be [maybe] etched as well.--

In the Claims:

Claims 38-45 have been added.

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